

REMARKS/ARGUMENTS

1. Summary of the Office Action

Claims 1-5 and 10-14 stand rejected under 35 U.S.C 103(a) as allegedly being unpatentable by U.S. patent no. 2002/0077035 A1 (hereinafter “Wang”) in view of U.S. patent no. 6,206,759 (hereinafter “Agarwal”).

Claims 1-5 and 10-14 stand rejected under 35 U.S.C 112 for allegedly failing to comply with the written description requirement by reciting an unsupported feature, namely, “a base support layer.”

Claims 1, 3 and 12 have been amended. The amendments are supported by the specification as filed. Accordingly, no new matter is added.

2. Response to § 103(a) Rejection

Claims 1-5 and 10-14 stand rejected under 35 U.S.C 103(a) as allegedly being unpatentable by Wang in view of Agarwal.

Although Wang discusses a polishing pad comprising a base layer and an ion exchange material on the base, Wang fails to disclose the presently claimed feature of “an ion exchange layer contiguously disposed in the base layer, wherein at least one of the base layer and the ion exchange layer is patterned” or “a contiguous resin layer coupled to the base layer and having ion exchange material embedded therein, wherein at least one of the base layer and the resin layer is patterned” as recited in claims 1 and 12, respectively.

Adding the teachings of Agarwal fails to cure Wang’s deficiencies. Agarwal, as indicated by the Examiner, discusses a polishing pad having a plurality of grooves through the cover layer 170, the intermediate layer 180 and a portion of the backing member 150 (col. 10, lines 2-4, Figure 8). Agarwal clearly illustrates in Figure 8 the grooves (pattern) are configured by cutting through and removing portions of each layer. Consequently, although the composite pad may be cut to include grooves, the layers described in Agarwal are not contiguous and therefore cannot have a contiguous patterned layer.

In sum, neither Wang alone or in combination with Agarwal discloses an ion exchange layer contiguously disposed in the base layer, wherein at least one of the base layer and the ion

exchange layer is patterned or a contiguous resin layer coupled to the base layer and having ion exchange material embedded therein, wherein at least one of the base layer and the resin layer is patterned, as recited in the present claims.

Because the dependent claims are deemed to include the limitations of the claim from which it depends, the arguments presented above also address the rejections against the dependent claims. Accordingly, the rejections against the independent and dependent claims have been addressed, and withdrawal of these rejections is respectfully requested.

3. Response to § 112 Rejection

The recited feature of "a base support layer" has been removed. Accordingly, the rejection under 35 U.S.C 112 is obviated.

4. Conclusion

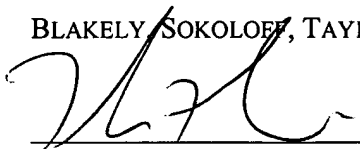
In view of all the foregoing reasons, applicants respectfully submit that the present application is in condition for allowance, and such allowance is earnestly solicited.

If there are any additional charges, please charge Deposit Account No. 02-2666. If a telephone interview would in any way expedite the prosecution of the present application, the Examiner is invited to contact Jaina Chua at (408) 947-8200 ext. 213.

Respectfully submitted,

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